

The following Listing of Claims will replace all prior versions, and listings, of claims in the application.

**LISTING OF CLAIMS:**

- 1.-6. (Cancelled)
7. (Currently Amended) A method for drying substrates, comprising the steps of:  
housing substrates within a processing container that contains a cleaning fluid;  
lowering a fluid face of the cleaning fluid within the processing container with respect to the substrates; and  
conveying a liquid drying fluid to an exhaust opening of a nozzle using a carrier gas, and simultaneously blowing the drying fluid and the carrier gas from the exhaust opening towards the fluid face of the cleaning fluid.
8. (Previously Presented) A device for drying substrates comprising:  
a processing container configured to contain a cleaning fluid, house substrates and lower a fluid face of the cleaning fluid within the processing container with respect to the substrates; and  
drying fluid supplying means for conveying a liquid drying fluid to an exhaust opening of a nozzle using a carrier gas, and for simultaneously blowing the drying fluid and the carrier gas from the exhaust opening towards the fluid face of the cleaning fluid.
9. (Previously Presented) The device for drying substrates as set forth in claim 8, wherein

the drying fluid supplying means comprises a first feed pipe for supplying the carrier gas to the nozzle and a second feed pipe for supplying the liquid drying fluid which is communicated to the first feed pipe.

10. (Previously Presented) The device for drying substrates as set forth in claim 8, wherein

the drying fluid supplying means comprises a first feed pipe for supplying the carrier gas to the nozzle and a second feed pipe for supplying the liquid drying fluid to the nozzle, the first feed pipe and the second feed pipe being independent from one another.

11.-14. (Cancelled)

15. (Previously Presented) A device for drying substrates comprising:  
a processing container configured to contain a cleaning fluid, house substrates and lower a fluid face of the cleaning fluid within the processing container with respect to the substrates; and

a drying fluid supplying mechanism configured and arranged to convey a liquid drying fluid to an exhaust opening of a nozzle using a carrier gas and simultaneously blow the drying fluid and the carrier gas from the exhaust opening towards the fluid face of the cleaning fluid.

16. (Previously Presented) The device for drying substrates as set forth in claim 15, wherein

the drying fluid supplying mechanism comprises a first feed pipe configured and arranged to supply the carrier gas to the nozzle and a second feed pipe configured and arranged to supply the liquid drying fluid which is communicated to the first feed pipe.

17. (Previously Presented) The device for drying substrate as set forth in claim 15, wherein

the drying fluid supplying mechanism comprises a first feed pipe configured and arranged to supply the carrier gas to the nozzle and a second feed pipe configured and arranged to supply the liquid drying fluid to the nozzle, the first feed pipe and the second feed pipe being independent from one another.